

**Amendments to the Claims:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

**Listing of Claims:**

1. (currently amended) A method for manufacturing a glass substrate for an information recording medium manufactured by polishing the surface of a raw glass plate, the method ~~being~~ characterized in that comprising:

~~the polishing is divided into two steps, a step for performing a first polishing process to roughly polish the surface of the raw glass plate to be smooth; and a step for performing a second polishing process to finely polish the surface of the roughly polished raw glass plate to be smoother;~~

~~wherein the second polishing process, using a polishing pad made of foam, is divided into~~ includes two stages[[,]]: ~~which are~~ pre-polishing with a polishing agent including abrasive grains of cerium oxide and post-polishing with a polishing agent including abrasive grains of silicon oxide; and

a rinsing process is performed between the pre-polishing and the post-polishing to rinse the raw glass plate after the pre-polishing with a washing liquid to wash away the abrasive grains collected in the polishing pad in pre-polishing during the rinsing process.

2. (currently amended) The method for manufacturing a glass substrate for the information recording medium according to claim 1, wherein the abrasive grains of cerium oxide have a mean grain diameter ~~(D<sub>50</sub>)~~ of 1.5  $\mu\text{m}$  or less and are smaller than a nap formation hole for the polishing pad.

3. (currently amended) The method for manufacturing a glass substrate for the information recording medium according to claim ~~1 or 2~~, ~~characterized in that~~ wherein the abrasive grains of silicon oxide have a grain diameter that is smaller than the grains of cerium oxide, a mean grain diameter (D<sub>50</sub>) of less than or equal to 0.2 $\mu\text{m}$ , and are smaller than the aperture diameter of the nap formation hole for the polishing pad.

4. (currently amended) The method for manufacturing a glass substrate for the information recording medium according to ~~any one of claim[[s]] 1 to 3~~, ~~characterized in that~~ wherein the second polishing process has a total task time of 7 to 45 minutes.

5. (currently amended) The method for manufacturing a glass substrate for the information recording medium according to ~~any one of claim[[s]] 1 to 4~~, ~~characterized in that~~ wherein the post-polishing has a task time of 1 to 40 minutes.

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6. (currently amended) The method for manufacturing a glass substrate for the information recording medium according to ~~any one of claim[[s]] 1 to 5, characterized in that~~ wherein the rinsing process has a task time of 1 to 20 minutes.

7. (currently amended) The method for manufacturing a glass substrate for the information recording medium according to ~~any one of claim[[s]] 1 to 6, characterized in that~~ wherein in the rinsing process, load applied to the raw glass plate by the polishing pad is lower than that in the pre-polishing.

8. (currently amended) The method for manufacturing a glass substrate for the information recording medium according to ~~any one of claim[[s]] 1 to 7, characterized in that~~ wherein in the rinsing process, load applied to the raw glass plate by the polishing pad is the same as or lower than that in the post-polishing.

9. (currently amended) The method for manufacturing a glass substrate for the information recording medium according to ~~any one of claim[[s]] 1 to 8, characterized in that~~ wherein load related to the rinsing process is 25 to 70 g/cm<sup>2</sup>.

10. (currently amended) A glass substrate for an information recording medium obtained from the manufacturing method according to ~~any one of claim[[s]] 1 to 9, wherein~~ wherein the glass plate ~~characterized in that~~ comprises:

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micro waviness height ~~(NRa)~~ of a surface measured by a three-dimensional surface structure analyzing microscope, with a measuring wavelength ~~(λ)~~ set at 0.2 to 1.4 mm, is 0.15 nm or less.

11. (currently amended) A polishing device for manufacturing a glass substrate for an information recording medium by polishing a surface of a raw glass plate, the polishing device ~~being characterized by~~ comprising:

a polishing pad made of a foam, in which the polishing pad ~~performing with~~ performs on the raw glass plate polishing that is divided into two stages, which are pre-polishing with a polishing agent including abrasive grains of cerium oxide and post-polishing with a polishing agent including abrasive grains of silicon oxide; and

a rinsing process performed between the pre-polishing and the post-polishing for rinsing the raw glass plate after the pre-polishing with a washing liquid, the polishing pad including a nap layer with an inner layer, having a plurality of independent bubbles, and an outer layer formed in its surface, having a plurality of nap formation holes with an extremely fine size compared to the independent bubbles, the nap formation holes being open at the surface of the polishing pad so that the abrasive grains collected in the polishing pad in the pre-polishing are washed away during the rinsing process.

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12. (currently amended) The polishing device according to claim 11, ~~characterized in that~~ wherein the nap formation holes of the polishing pad have a hole diameter of 2  $\mu\text{m}$  or greater and 20  $\mu\text{m}$  or less, and a depth of 2  $\mu\text{m}$  or greater and 100  $\mu\text{m}$  or less.

13. (currently amended) The polishing device according to claim 11 ~~or 12~~, further ~~being characterized by~~ comprising a lower mass and an upper mass arranged rotatably about a rotation shaft, and a carrier, arranged between the upper bed and the lower bed, for supporting a plurality of raw glass plates, the surfaces of the raw glass plate being polished by the polishing pad by rotating the upper bed and the lower bed in a state in which the polishing pad is attached to the lower bed and the upper bed as necessary.

14. (new) The method for manufacturing a glass substrate for the information recording medium according to claim 1, wherein the abrasive grains of silicon oxide have a grain diameter that is smaller than the grains of cerium oxide, a mean grain diameter of less than or equal to 0.2 $\mu\text{m}$ , and are smaller than the aperture diameter of a nap formation hole for the polishing pad.

15. (new) The method for manufacturing a glass substrate for the information recording medium according to claim 2

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wherein the second polishing process has a total task time of 7 to 45 minutes.

16. (new) The method for manufacturing a glass substrate for the information recording medium according to claim 2, wherein the post-polishing has a task time of 1 to 40 minutes.

17. (new) The method for manufacturing a glass substrate for the information recording medium according to claim 2 wherein the rinsing process has a task time of 1 to 20 minutes.

18. (new) The method for manufacturing a glass substrate for the information recording medium according to claim 2, wherein in the rinsing process, load applied to the raw glass plate by the polishing pad is lower than that in the pre-polishing.

19. (new) The method for manufacturing a glass substrate for the information recording medium according to claim 2, wherein in the rinsing process, load applied to the raw glass plate by the polishing pad is the same as or lower than that in the post-polishing.

20. (new) The method for manufacturing a glass substrate for the information recording medium according to claim 2, wherein load related to the rinsing process is 25 to 70 g/cm<sup>2</sup>.